

<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>	<b>Docket Number (Optional)</b> <b>TWI-23710</b>	<b>Application Number</b> <b>NEW</b>
	<b>Applicant(s)</b> <b>Yia-Chung Chang et al.</b>	
	<b>Filing Date</b> <b>HEREWITH</b>	<b>Group Art Unit</b> <b>Unknown</b>

**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
KG	*AA	5,607,800	03/04/97	Ziger	430	8	02/15/95
	*AB	5,739,909	04/14/98	Blayo et al.	356	369	10/10/95
	*AC	5,867,276	02/02/99	McNeil et al.	356	445	03/07/97
	*AD	5,889,593	03/30/99	Bareket	356	445	02/26/97
	*AE	5,910,842	06/08/99	Piwonka-Corle et al.	356	369	11/27/96
	*AF	5,963,329	10/05/99	Conrad et al.	356	372	10/31/97
	*AG	6,268,916	07/31/01	Lee et al.	356	369	05/11/99
	*AH	6,429,943	08/06/02	Opsal et al.	356	625	03/27/01
	*AI	6,483,580	11/19/02	Xu et al.	356	300	03/06/98
	*AJ	2001/0051856	12/13/01	Niu et al.	702	57	01/17/01
	*AK	2002/0158193	10/31/02	Sezginer et al.	250	237	02/12/02
KG	*AL	2003/0147086	08/07/03	Rosencwaig et al.	356	601	09/13/02

**FOREIGN PATENT DOCUMENTS**

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
KG	AM	WO 03/009063	01/30/03	PCT	G03F	7/20		

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KG	AN	J. Opsal et al., "Contact hole inspection by real-time optical CD metrology", Metrology, Inspection, and Process Control for Microlithography XVII, Daniel J. Herr, Editor, Proceedings of SPIE Vol. 5038 (2003), pp. 597-603.
KG	AO	J. Bischoff et al., "Optical Digital Profilometry applications on contact holes", Metrology, Inspection, and Process Control for Microlithography XVII, Daniel J. Herr, Editor, Proceedings of SPIE Vol. 5038 (2003), pp. 1080-1088.
KG	AP	B.D. Bunday et al., "CD-SEM Measurement of Line Edge Roughness Test Patterns for 193 nm Lithography", Metrology, Inspection, and Process Control for Microlithography XVII, Daniel J. Herr, Editor, Proceedings of SPIE Vol. 5038 (2003), pp. 674-688.

<b>Examiner</b> /Kara Geisel/ (06/20/2006)	<b>Date Considered</b>
<b>Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</b>	



**INFORMATION DISCLOSURE CITATION**  
(Use several sheets if necessary)

Docket Number (Optional)

**TWI-32710**

Application Number

**10/795,915**

Applicant(s)

**Via-Chung Chang et al.**

Filing Date

**March 8, 2004**

Group Art Unit

**2877**

**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE

**FOREIGN PATENT DOCUMENTS**

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
KG	BA	WO 03/075041 A2	09/12/2003	PCT	G02B			

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(Including Author, Title, Date, Pertinent Pages, Etc.)


Examiner /Kara Geisel/ (06/20/2006)

Date Considered

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.